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(54) **Title:** DISTURBANCE COMPENSATION FOR SUBSTRATE PROCESSING RECIPES

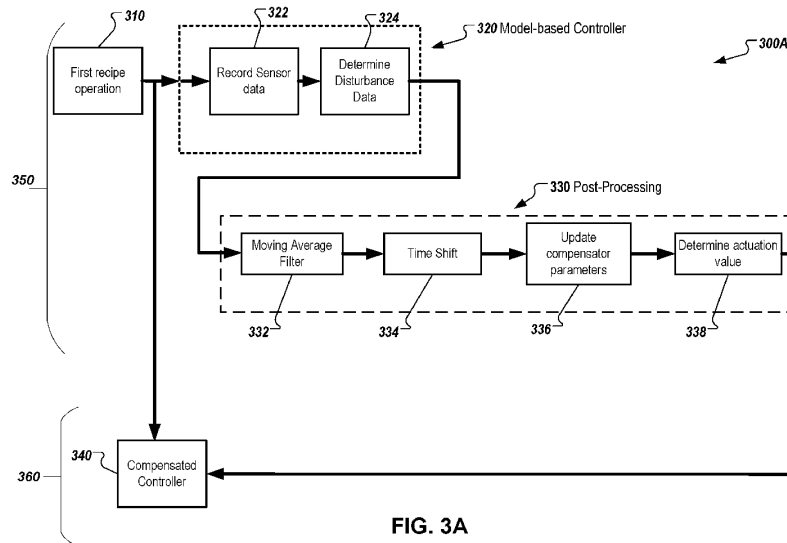


FIG. 3A

(57) **Abstract:** A method includes receiving first sensor data associated with a first iteration of a first recipe operation of a substrate processing recipe. The method further includes determining disturbance data, the disturbance data being a difference between the first sensor data and first setpoint data of the first recipe operation. The method further includes determining, based at least in part on the disturbance data, a first actuation value associated with one or more components of a processing chamber. Actuation of the one or more components according to the first actuation value compensates for the disturbance data. The method further includes causing the actuation of the one or more components based on the first actuation value during a subsequent iteration of the first recipe operation of the substrate processing recipe to compensate for the disturbance data.

[Continued on next page]

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- *as to the applicant's entitlement to claim the priority of the earlier application (Rule 4.17(iii))*

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